

One days workshop

on

**Dynamic Light Scattering Technology & Rheology
and its interlinked relation between them**

Date : 18th January 2018



Gauhati University

This workshop is being organized by Department Of Bioengineering and Technology, Gauhati University Institute Of Science & Technology, Gauhati University and Aimil Instrumentation & Technology. for hand on training on Zetasizer along with the basic understanding the need and implementation in Nanotechnology. The training course aims to help the participants to determined physico-chemical parameters like particles size and zeta potential. Classroom format: lectures & hands on training.

Topics

1st half : Basics of Dynamic Light Scattering Technology and Rheology

2nd half: Hands on Training on Zetasizer Instrument

Instructors: **Dr. Anand Tadas**

Who Can Apply

This workshop is open Preferably for PhD student and M.Sc. or M.tech. students

Number of Participants is Limited to 20

Registration fees: Free, participants will not be provided any fooding

Application forms can be downloaded from:

Gauhati.ac.in

Filled up application forms should be sent via e-mail to both contact addresses given below.

Deadline for Receipt of Applications: 16th January 2018

Contact addresses:

Dr. Subhash Medhi, Assistant professor ,Department of Bioengineering and Technology GUIST, Gauhati University.

Email:

subhash_medhi@rediffmail.com

Organized by: Aimil Instrumentation & Technology & Department Of Bioengineering & Technology, Gauhati University Institute Of Science & Technology Gauhati University

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APPLICATION FORM

1. Name of applicant:
(In block letter)
2. I. Age (in years):
II. Sex:
3. I. Email address:
II. Phone No:
4. Current affiliation:
6. Position:
7. Highest academic degree obtained and the subject in which obtained:

8. Describe your current work in five sentences and why you want to pursue this workshop :

Date:

Place:.....

Signature of applicant